

1st test

10525429f.trn

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NEWS 2 JAN 08 CHEMLIST enhanced with New Zealand Inventory of Chemicals
NEWS 3 JAN 16 CA/CAPLUS Company Name Thesaurus enhanced and reloaded
NEWS 4 JAN 16 IPC version 2007.01 thesaurus available on STN
NEWS 5 JAN 16 WPIDS/WPINDEX/WPIX enhanced with IPC 8 reclassification data
NEWS 6 JAN 22 CA/CAPLUS updated with revised CAS roles
NEWS 7 JAN 22 CA/CAPLUS enhanced with patent applications from India
NEWS 8 JAN 29 PHAR reloaded with new search and display fields
NEWS 9 JAN 29 CAS Registry Number crossover limit increased to 300,000 in multiple databases
NEWS 10 FEB 15 PATDPASPC enhanced with Drug Approval numbers
NEWS 11 FEB 15 RUSSIAPAT enhanced with pre-1994 records
NEWS 12 FEB 23 KOREAPAT enhanced with IPC 8 features and functionality
NEWS 13 FEB 26 MEDLINE reloaded with enhancements
NEWS 14 FEB 26 EMBASE enhanced with Clinical Trial Number field
NEWS 15 FEB 26 TOXCENTER enhanced with reloaded MEDLINE
NEWS 16 FEB 26 IFICDB/IFIPAT/IFIUDB reloaded with enhancements
NEWS 17 FEB 26 CAS Registry Number crossover limit increased from 10,000 to 300,000 in multiple databases
NEWS 18 MAR 15 WPIDS/WPIX enhanced with new FRAGHITSTR display format
NEWS 19 MAR 16 CASREACT coverage extended
NEWS 20 MAR 20 MARPAT now updated daily
NEWS 21 MAR 22 LWPI reloaded
NEWS 22 MAR 30 RDISCLOSURE reloaded with enhancements
NEWS 23 MAR 30 INPADOCDB will replace INPADOC on STN
NEWS 24 APR 02 JICST-EPLUS removed from database clusters and STN

NEWS EXPRESS NOVEMBER 10 CURRENT WINDOWS VERSION IS V8.01c, CURRENT MACINTOSH VERSION IS V6.0c(ENG) AND V6.0Jc(JP), AND CURRENT DISCOVER FILE IS DATED 25 SEPTEMBER 2006.

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* * * * * STN Columbus * * * * *

FILE 'HOME' ENTERED AT 11:54:08 ON 18 APR 2007

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COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

1.05

1.05

FILE 'REGISTRY' ENTERED AT 11:57:01 ON 18 APR 2007

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STRUCTURE FILE UPDATES: 16 APR 2007 HIGHEST RN 930395-50-9

DICTIONARY FILE UPDATES: 16 APR 2007 HIGHEST RN 930395-50-9

New CAS Information Use Policies, enter HELP USAGETERMS for details.

TSCA INFORMATION NOW CURRENT THROUGH December 2, 2006

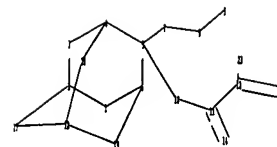
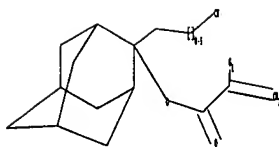
Please note that search-term pricing does apply when conducting SmartSELECT searches.

REGISTRY includes numerically searchable data for experimental and predicted properties as well as tags indicating availability of experimental property data in the original document. For information on property searching in REGISTRY, refer to:

<http://www.cas.org/ONLINE/UG/regprops.html>

=>

Uploading C:\Program Files\Stnexp\Queries\10525429f.str



chain nodes :

7 8 9 10 11 12 13 14 23

ring nodes :

1 2 3 4 5 6 17 18 19 20

chain bonds :

5-7 5-10 7-8 8-9 10-11 11-12 11-14 12-13 12-23

ring bonds :

1-2 1-6 2-3 2-17 3-4 4-5 4-20 5-6 6-19 17-18 18-19 18-20

exact/norm bonds :

5-10 10-11 11-14 12-23

exact bonds :

1-2 1-6 2-3 2-17 3-4 4-5 4-20 5-6 5-7 6-19 7-8 8-9 11-12 12-13 17-18
18-19 18-20

isolated ring systems :

containing 1 :

G1:H,CH3,CF3

Match level :

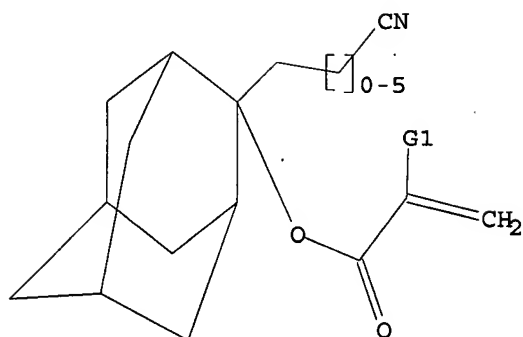
1:Atom 2:Atom 3:Atom 4:Atom 5:Atom 6:Atom 7:CLASS 8:CLASS 9:CLASS 10:CLASS
11:CLASS 12:CLASS 13:CLASS 14:CLASS 17:Atom 18:Atom 19:Atom 20:Atom
23:CLASS

L1 STRUCTURE UPLOADED

=> d l1

L1 HAS NO ANSWERS

L1 STR



G1 H, Me, CF3

Structure attributes must be viewed using STN Express query preparation.

=> s l1

SAMPLE SEARCH INITIATED 11:57:18 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 1 TO ITERATE

100.0% PROCESSED 1 ITERATIONS

1 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
 BATCH **COMPLETE**

PROJECTED ITERATIONS: 1 TO 80

PROJECTED ANSWERS: 1 TO 80

L2 1 SEA SSS SAM L1

=> s l1 sss full

FULL SEARCH INITIATED 11:57:25 FILE 'REGISTRY'

FULL SCREEN SEARCH COMPLETED - 47 TO ITERATE

100.0% PROCESSED 47 ITERATIONS

SEARCH TIME: 00.00.01

18 ANSWERS

L3 18 SEA SSS FUL L1

=> FIL HCAPLUS

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

172.10

173.15

FILE 'HCAPLUS' ENTERED AT 11:57:32 ON 18 APR 2007

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FILE COVERS 1907 - 18 Apr 2007 VOL 146 ISS 17
FILE LAST UPDATED: 16 Apr 2007 (20070416/ED)

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This file contains CAS Registry Numbers for easy and accurate substance identification.

=> s l3

L4 8 L3

=> d l4 ibib abs hitstr tot

L4 ANSWER 1 OF 8 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2006:1030320 HCAPLUS

DOCUMENT NUMBER: 145:377669

TITLE: Manufacture of alkali metal 2-cyanomethyl-2-adamantanolates and 2-cyanomethyl-2-adamantyl unsaturated esters

INVENTOR(S): Maehara, Takayuki

PATENT ASSIGNEE(S): Tokuyama Corp., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 18pp.

CODEN: JKXXAF

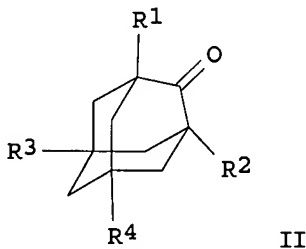
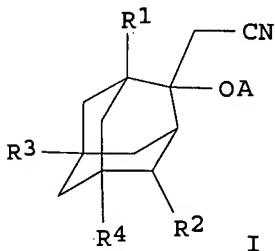
DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

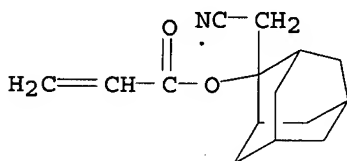
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2006265106	A	20061005	JP 2005-81140	20050322
PRIORITY APPLN. INFO.: GI			JP 2005-81140	20050322

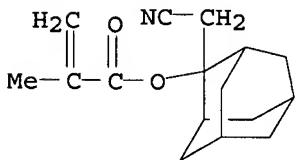


AB The adamantanolates I (R1-R4 = H, C1-5 alkyl; A = alkali metal) are manufactured by treatment of 2-adamantanones II (R1-R4 = same as above) with MeCN and NAR5R6 (R5, R6 = H, C1-5 alkyl; A = alkali metal). The esters are useful for resists. Thus, (iso-Pr)₂NH was treated with BuLi in THF, treated with 2-adamantanone (III) and MeCN to give a solution containing a reaction mixture containing Li 2-cyanomethyl-2-adamantanolate (IV) 90, III 7, and 2-cyanomethyleneadamantane (V) 3%. The solution was dropped into a THF solution containing methacrylic anhydride to give an oil containing III 7, IV 18, V

8, and 2-cyanomethyl-2-adamantyl methacrylate 67%.
 IT 875924-12-2P
 RL: IMF (Industrial manufacture); PREP (Preparation)
 (manufacture of (cyanomethyl)adamantyl unsatd. esters for resists from
 adamantanones via alkali metal (cyanomethyl)adamantanolates)
 RN 875924-12-2 HCAPLUS
 CN 2-Propenoic acid, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester (9CI)
 (CA INDEX NAME)



IT 853644-75-4P, 2-Cyanomethyl-2-adamantyl methacrylate
 RL: IMF (Industrial manufacture); PUR (Purification or recovery); PREP
 (Preparation)
 (manufacture of (cyanomethyl)adamantyl unsatd. esters for resists from
 adamantanones via alkali metal (cyanomethyl)adamantanolates)
 RN 853644-75-4 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl
 ester (9CI) (CA INDEX NAME)



L4 ANSWER 2 OF 8 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 2006:941254 HCAPLUS
 DOCUMENT NUMBER: 145:324980
 TITLE: Deep-UV or electron-beam lithography, resists and
 polymers therefor, and manufacture thereof
 INVENTOR(S): Momose, Akira; Ueda, Shoji
 PATENT ASSIGNEE(S): Mitsubishi Rayon Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 76pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2006241233	A	20060914	JP 2005-56078	20050301
PRIORITY APPLN. INFO.:			JP 2005-56078	20050301

AB The polymers have repeating units containing acid-leaving groups formed from
 polymerization of monomers J(XSH)_n [X = single bond, B11, SB11, OSiB13B14 (B11
 =
 C1-20 hydrocarbylene; B12 = H, C1-10 alkyl; B13, B14 = H, C1-10 alkyl); n
 = 3-24; J = n-valent hydrocarbon] in the presence of initiators. Resists

containing the polymers are applied on substrates, exposed to ≤ 250 -nm light, and developed to form patterns with small line edge roughness.

IT 909100-43-2P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(deep-UV or electron-beam resists containing starburst polymers having acid-leaving groups)

RN 909100-43-2 HCAPLUS

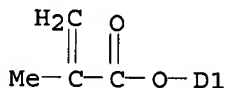
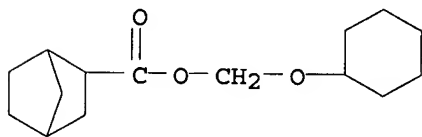
CN Bicyclo[2.2.1]heptane-2-carboxylic acid, 5(or 6)-[(2-methyl-1-oxo-2-propenyl)oxy]-, (cyclohexyloxy)methyl ester, polymer with 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 870136-27-9

CMF C19 H28 O5

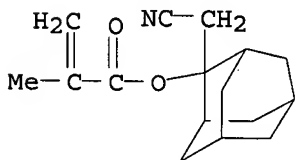
CCI IDS



CM 2

CRN 853644-75-4

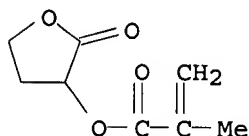
CMF C16 H21 N O2



CM 3

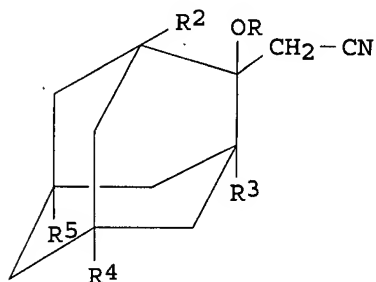
CRN 195000-66-9

CMF C8 H10 O4

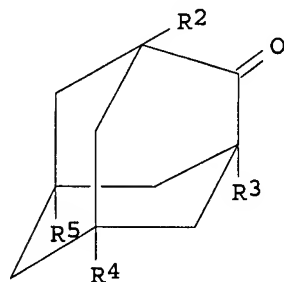


L4 ANSWER 3 OF 8 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 2006:141410 HCAPLUS
 DOCUMENT NUMBER: 144:213169
 TITLE: Preparation of 2-cyanomethyl-2-adamantyl esters and their intermediates
 INVENTOR(S): Maehara, Takayuki
 PATENT ASSIGNEE(S): Tokuyama Corp., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 21 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2006045161	A	20060216	JP 2004-231406	20040806
PRIORITY APPLN. INFO.:			JP 2004-231406	20040806
OTHER SOURCE(S):	MARPAT	144:213169		
GI				



I



III

AB The esters [R = COR1; R1 = (un)substituted polymerizable unsatd. hydrocarbyl; R2-R5 = H, C1-5 alkyl], useful as monomers for functional materials and electronic materials, are prepared by reacting I (R = H, alkali metal; R2-R5 = same as above) (II) with polymerizable unsatd. carboxylic anhydrides or halides. II (R = H) are prepared by reacting 2-adamantanones III (R2-R5 = same as above) with MeCN in the presence of alkali metals and hydrolyzing the resulting II (R = alkali metal). Thus, Li was added to a mixture of 2-adamantanone, MeCN, and THF in 3 portions and the reaction mixture was stirred at 45° for 5 h. The reaction solution containing Li 2-cyanomethyl-2-adamantanolate was added dropwise to a mixture of methacrylic anhydride and THF at ≤10° and the reaction mixture was stirred for 1 h to give 2-cyanomethyl-2-adamantyl methacrylate with purity 92%.

IT 853644-75-4P, 2-Cyanomethyl-2-adamantyl methacrylate
 875924-12-2P

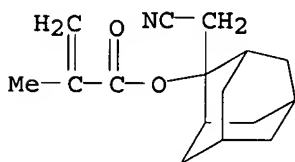
RL: IMF (Industrial manufacture); PUR (Purification or recovery); SPN

(Synthetic preparation); PREP (Preparation)

(preparation of polymerizable (cyanomethyl)adamantyl esters by addition of MeCN to adamantanonones using alkali metals, hydrolysis of alcoholates, and esterification)

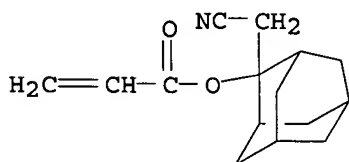
RN 853644-75-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester (9CI) (CA INDEX NAME)



RN 875924-12-2 HCAPLUS

CN 2-Propenoic acid, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester (9CI) (CA INDEX NAME)



L4 ANSWER 4 OF 8 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2006:75721 HCAPLUS

DOCUMENT NUMBER: 144:160277

TITLE: Photoresists, cyano-substituted (meth)acrylate polymers therefor, their monomers, and synthesis thereof

INVENTOR(S): Shimizu, Shigeru

PATENT ASSIGNEE(S): Mitsubishi Rayon Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 16 pp.

CODEN: JKXXAF

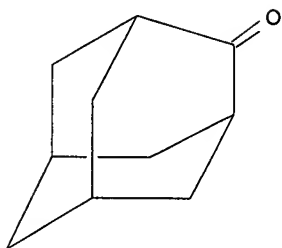
DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

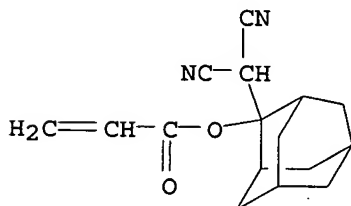
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2006022165	A	20060126	JP 2004-199767	20040706
PRIORITY APPLN. INFO.: GI			JP 2004-199767	20040706

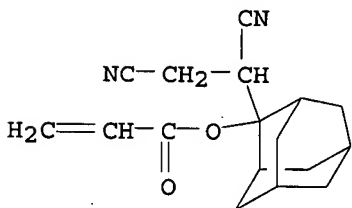


I

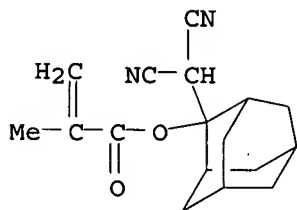
- AB Carbonyl compds. I are reacted with malondinitrile in the presence of bases and then with (meth)acrylic acid derivs. to afford esters represented by $\text{H}_2\text{C}:\text{CRCO}_2\text{G}$ ($\text{G} = \text{Q1-Q10}$; $\text{R} = \text{H, Me}$). Polymers of the esters and photoresists containing the polymers are further claimed. The polymers exhibit good adhesion to substrates, dry etching resistance, and high sensitivity.
- IT 873805-99-3P 873806-00-9P 873806-09-8P
873806-10-1P
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(monomers; synthesis of (meth)acrylates having cyano-substituted alicyclic groups for pos. photoresists)
- RN 873805-99-3 HCAPLUS
- CN 2-Propenoic acid, 2-(dicyanomethyl)tricyclo[3.3.1.1.3,7]dec-2-yl ester (9CI) (CA INDEX NAME)



- RN 873806-00-9 HCAPLUS
- CN 2-Propenoic acid, 2-(1,2-dicyanoethyl)tricyclo[3.3.1.1.3,7]dec-2-yl ester (9CI) (CA INDEX NAME)

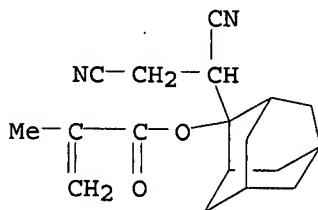


- RN 873806-09-8 HCAPLUS
- CN 2-Propenoic acid, 2-methyl-, 2-(dicyanomethyl)tricyclo[3.3.1.1.3,7]dec-2-yl ester (9CI) (CA INDEX NAME)



RN 873806-10-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(1,2-dicyanoethyl)tricyclo[3.3.1.1.3,7]dec-2-yl ester (9CI) (CA INDEX NAME)



IT 873806-76-9P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(resist components; synthesis of (meth)acrylates having cyano-substituted alicyclic groups for pos. photoresists)

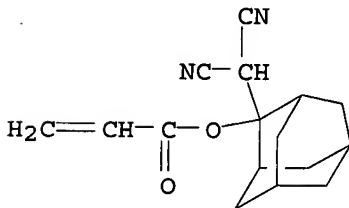
RN 873806-76-9 HCAPLUS

CN 2-Propenoic acid, 2-(dicyanomethyl)tricyclo[3.3.1.1.3,7]dec-2-yl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 873805-99-3

CMF C16 H18 N2 O2



11/11/07

L4 ANSWER 5 OF 8 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2005:1154518 HCAPLUS

DOCUMENT NUMBER: 143:422757

TITLE: Adamantane derivative and process for producing the same

INVENTOR(S): Ito, Hajime; Tanaka, Shinji

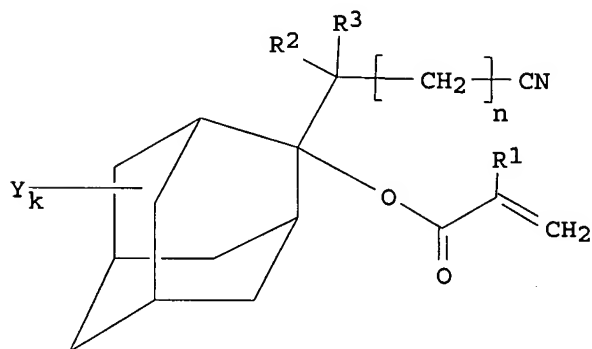
PATENT ASSIGNEE(S): Idemitsu Kosan Co., Ltd., Japan

SOURCE: PCT Int. Appl., 20 pp.

CODEN: PIXXD2

DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

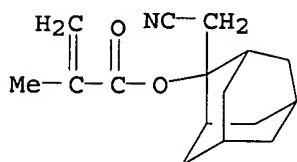
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2005100304	A1	20051027	WO 2004-JP14835	20041007
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW				
RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
CN 1780812	A	20060531	CN 2004-80000851	20041007
EP 1731504	A1	20061213	EP 2004-792132	20041007
R: BE, DE, FR, GB				
US 2006167302	A1	20060727	US 2005-525429	20050223
JP 2005314383	A	20051110	JP 2005-92620	20050328
PRIORITY APPLN. INFO.:			JP 2004-109743	A 20040402
			WO 2004-JP14835	W 20041007
OTHER SOURCE(S):		MARPAT 143:422757		
GI				



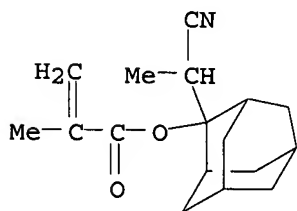
I

AB Title adamantane derivative is characterized by having a structure represented by the general formula (I): wherein R1 is H, Me, or trifluoromethyl; Y is C1-C10 alkyl, halogen, H, or =O (2 groups of Y); R2 and R3 are H or, C1-C10 alkyl, k is 0-14; and n is 0-3. The process for producing the adamantane derivative I with n is 0 (e.g., 2-cyanomethyl-2-adamantyl methacrylate) comprises reacting an adamantanone compound (e.g., adamantanone) with a nitrile compound (e.g., acetonitrile) and then with an acid halide or acid anhydride of a (meth)acrylic acid compound (e.g., methacrylic anhydride). The adamantane derivative I is a novel adamantane derivative useful as a monomer for a functional resin such as a photosensitive resin for use in the field of photolithog. It can be efficiently produced by the process.

IT 853644-75-4P, 2-Cyanomethyl-2-adamantyl methacrylate
 868135-90-4P, 2-(1-Cyanoethyl)-2-adamantyl methacrylate
 RL: IMF (Industrial manufacture); PRP (Properties); PREP (Preparation)
 (production of adamantane derivative as monomer for photosensitive resin for
 use in the field of photolithog.)
 RN 853644-75-4 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl
 ester (9CI) (CA INDEX NAME)



RN 868135-90-4 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-(1-cyanoethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl
 ester (9CI) (CA INDEX NAME)



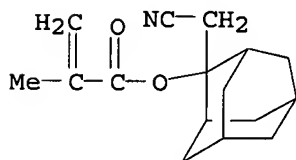
REFERENCE COUNT: 2 THERE ARE 2 CITED REFERENCES AVAILABLE FOR THIS
 RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L4 ANSWER 6 OF 8 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 2005:1026891 HCAPLUS
 DOCUMENT NUMBER: 143:336279
 TITLE: Aromatic-free and fluorine-free photoresists and
 photoacid generators containing pendant cyanoadamantyl
 methacrylate polymers
 INVENTOR(S): Bae, Young C.; Kavanagh, Robert J.
 PATENT ASSIGNEE(S): Rohm and Haas Electronic Materials, L.L.C., USA
 SOURCE: PCT Int. Appl., 43 pp.
 CODEN: PIXXD2
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 2
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2005086901	A2	20050922	WO 2005-US7910	20050308
WO 2005086901	A3	20061026		

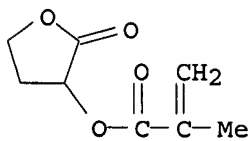
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 GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC,
 LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI,
 NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM,

SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
 RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM,
 AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK,
 EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT,
 RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML,
 MR, NE, SN, TD, TG
 EP 1586944 A1 20051019 EP 2005-251340 20050307
 R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
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 BA, HR, IS, YU
 US 2005208418 A1 20050922 US 2005-75545 20050308
 JP 2005281307 A 20051013 JP 2005-63253 20050308
 KR 2006043495 A 20060515 KR 2005-18985 20050308
 CN 1670014 A 20050921 CN 2005-10054530 20050309
 PRIORITY APPLN. INFO.: US 2004-551448P P 20040308
 US 2004-551880P P 20040309
 AB Aromatic group-free and fluorine-free photoresist compns. containing ≥ 1
 photoacid generator compds. and a resin component, in which the resin
 component consists of a polymer that contains a cyanoadamantyl group
 consisting of a cyano group, preferably pendant at the 2- or 4-position of
 an adamantyl group. Preferred polymers are used in photoresists imaged at
 wavelengths < 250 nm, especially 193-248 nm.
 IT 853644-80-1P 865346-06-1P 865346-07-2P
 865346-08-3P
 RL: SPN (Synthetic preparation); TEM (Technical or engineered material
 use); PREP (Preparation); USES (Uses)
 (photoresist; aromatic-free and fluorine-free photoresists and photoacid
 generators containing pendant cyanoadamantyl methacrylate polymers)
 RN 853644-80-1 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl
 ester, polymer with 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl
 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate
 (9CI) (CA INDEX NAME)
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 CRN 853644-75-4
 CMF C16 H21 N O2



CM 2
 CRN 195000-66-9
 CMF C8 H10 O4

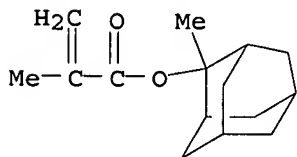
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CM 3

CRN 177080-67-0

CMF C15 H22 O2



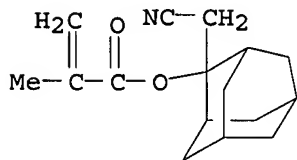
RN 865346-06-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester, polymer with 1-ethylcyclopentyl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 853644-75-4

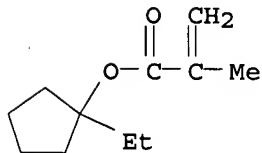
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CM 2

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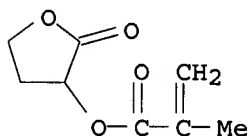
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CM 3

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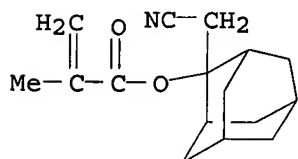
CRN 195000-66-9
CMF C8 H10 O4



RN 865346-07-2 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester, polymer with 2-ethyltricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

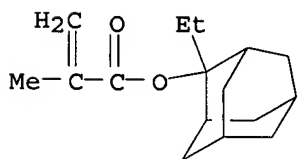
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CRN 853644-75-4
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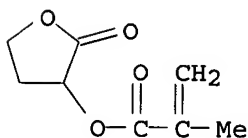
CM 2

CRN 209982-56-9
CMF C16 H24 O2



CM 3

CRN 195000-66-9
CMF C8 H10 O4



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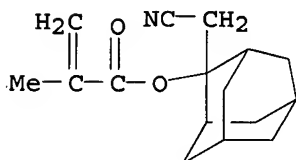
RN 865346-08-3 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with bicyclo[2.2.1]hept-2-ene,
2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate and
1-ethylcyclopentyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 853644-75-4

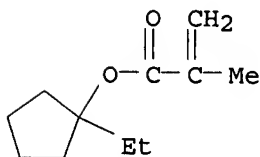
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CM 2

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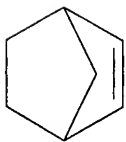
CMF C11 H18 O2



CM 3

CRN 498-66-8

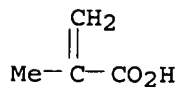
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CM 4

CRN 79-41-4

CMF C4 H6 O2



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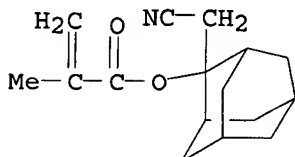
IT 853644-75-4P

RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)

(synthesis and polymerization of; aromatic-free and fluorine-free photoresists and photoacid generators containing pendant cyanoadamantyl methacrylate polymers)

RN 853644-75-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester (9CI) (CA INDEX NAME)



L4 ANSWER 7 OF 8 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2005:998776 HCAPLUS

DOCUMENT NUMBER: 143:295593

TITLE: Photoresists comprising cyano adamantyl moiety-containing polymers

INVENTOR(S): Bae, Young C.; Kananagh, Robert J.

PATENT ASSIGNEE(S): Rohm and Haas Electronic Materials, L.L.C., USA

SOURCE: Eur. Pat. Appl., 21 pp.

CODEN: EPXXDW

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1574903	A1	20050914	EP 2005-251342	20050307
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, BA, HR, IS, YU				

JP 2005258438	A	20050922	JP 2005-61914	20050307
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US 2005208417	A1	20050922	US 2005-75544	20050308
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CN 1683997	A	20051019	CN 2005-10054399	20050308
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KR 2006043494	A	20060515	KR 2005-18984	20050308
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PRIORITY APPLN. INFO.:	US 2004-551448P	P	20040308
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AB Cyano adamantyl compds., polymers that comprise polymerized units of such compds., and photoresist compns. that comprise such polymers are provided. Preferred polymers of the invention are employed in photoresists imaged at wavelengths less than 250 nm such as 248 nm and 193 nm.

IT 864367-15-7P 864367-16-8P

RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(preparation of cyano adamantyl moiety-containing polymers for photoresists)

RN 864367-15-7 HCAPLUS

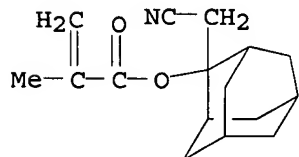
CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester, polymer with 3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

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CM 1

CRN 853644-75-4

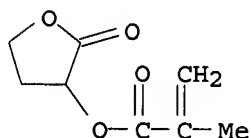
CMF C16 H21 N O2



CM 2

CRN 195000-66-9

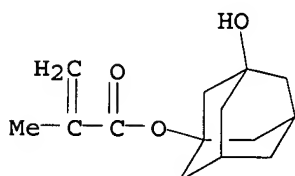
CMF C8 H10 O4



CM 3

CRN 115372-36-6

CMF C14 H20 O3



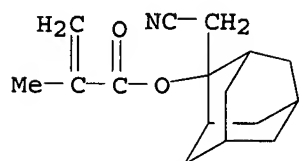
RN 864367-16-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 5-cyanobicyclo[2.2.1]hept-2-yl ester, polymer with 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 853644-75-4

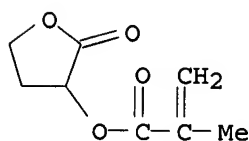
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CM 2

CRN 195000-66-9

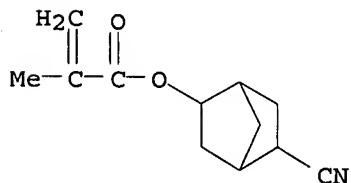
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CM 3

CRN 123118-84-3

CMF C12 H15 N O2



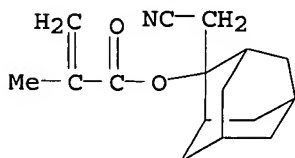
IT 853644-75-4P

RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)

(preparation of cyano adamantyl moiety-containing polymers for photoresists)

RN 853644-75-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester (9CI) (CA INDEX NAME)



REFERENCE COUNT:

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THERE ARE 2 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L4 ANSWER 8 OF 8 HCAPLUS COPYRIGHT 2007 ACS on STN

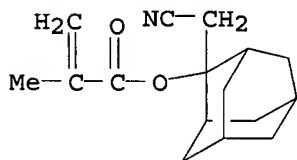
ACCESSION NUMBER: 2005:522122 HCAPLUS
 DOCUMENT NUMBER: 143:44193
 TITLE: Preparation of (meth)acrylates and their raw materials for polymers with good sensitivity, resolution, and dry etching resistance.
 INVENTOR(S): Otake, Atsushi
 PATENT ASSIGNEE(S): Mitsubishi Rayon Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 42 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005154427	A	20050616	JP 2004-314525	20041028
PRIORITY APPLN. INFO.:			JP 2003-372356	A 20031031

AB The present invention relates to β -cyanohydrin analogs CR1R2(OX)CN, wherein X = H, alkali metal, or magnesium halide; R1 = C1-6 alkyl having (alkyl substituted) C4-16 cyclic hydrocarbon group; R2 = C1-6 alkyl (R1 and R2 form (alkyl substituted) C4-16 cyclo hydrocarbon group by bonding carbon atoms); and the alkyl and cyclic hydrocarbon groups may be substituted with hydroxy, carboxy, C1-6 alkoxy or acyl, or carboxy group esterified with C1-6 alcs. Thus, 2.05 g acetonitrile and 7.6 g camphor were reacted at 0° in the presence of butyllithium, 5.2 h methacryloyl chloride was added therein at -40° and reacted at -40° for 2 h to give a cyano-containing methacrylate, 52.2 parts of which was copolymerized with 93.7 parts 2-methacryloyloxy-2-methyladamantane and 68.1 parts α -methacryloyloxy- γ -butyrolactone in the presence of AIBN to give a copolymer with Mw 7600, polydispersity 1.75, good sensitivity, resolution, and dry etching resistance when used as a photoresist material.

IT 853644-75-4P
 RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
 (monomer; preparation of (meth)acrylates and their raw materials for polymers with good sensitivity, resolution, and dry etching resistance.)

RN 853644-75-4 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester (9CI) (CA INDEX NAME)



IT 853644-80-1P 853644-83-4P 853735-28-1P
 RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (preparation of (meth)acrylates and their raw materials for polymers with good sensitivity, resolution, and dry etching resistance.)

RN 853644-80-1 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester, polymer with 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate

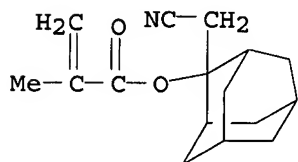
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(9CI) (CA INDEX NAME)

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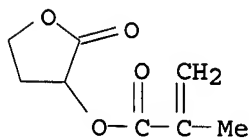
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CM 2

CRN 195000-66-9

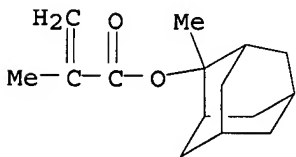
CMF C8 H10 O4



CM 3

CRN 177080-67-0

CMF C15 H22 O2



RN 853644-83-4 HCAPLUS

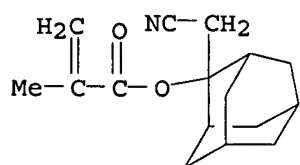
CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1.3,7]dec-2-yl ester, polymer with 1-methylcyclohexyl 2-methyl-2-propenoate, octahydro-1(or 3)-oxo-4,7-methanoisobenzofuran-5-yl 2-methyl-2-propenoate and tricyclo[3.3.1.1.3,7]dec-1-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 853644-75-4

CMF C16 H21 N O2

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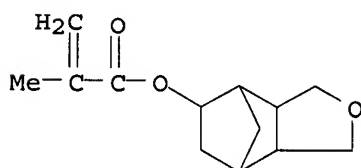


CM 2

CRN 436852-34-5

CMF C13 H16 O4

CCI IDS

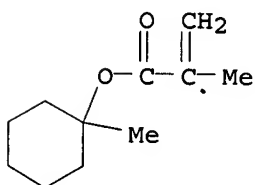


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CM 3

CRN 76392-14-8

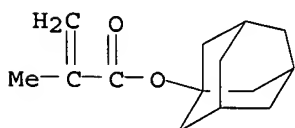
CMF C11 H18 O2



CM 4

CRN 16887-36-8

CMF C14 H20 O2



RN 853735-28-1 HCAPLUS

04/18/2007

Page 23

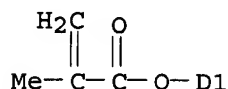
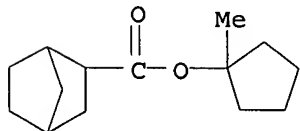
CN Bicyclo[2.2.1]heptane-2-carboxylic acid, 5(or 6)-[(2-methyl-1-oxo-2-propenyl)oxyl-, 1-methylcyclopentyl ester, polymer with 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 853735-27-0

CMF C18 H26 O4

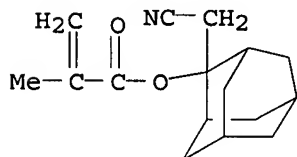
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CM 2

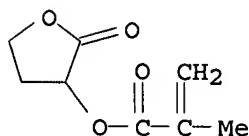
CRN 853644-75-4

CMF C16 H21 N O2



CM 3

CRN 195000-66-9

CMFC8H10O4

IT 853644-77-6P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(preparation of (meth)acrylates and their raw materials for polymers with good sensitivity, resolution, and dry etching resistance.)

RN 853644-77-6 HCAPLUS

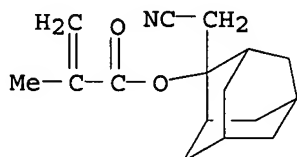
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CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 853644-75-4

CMF C16 H21 N O2



=> FIL REGISTRY

COST IN U.S. DOLLARS

SINCE FILE	TOTAL
ENTRY	SESSION
60.36	233.51

FULL ESTIMATED COST

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)

SINCE FILE	TOTAL
ENTRY	SESSION
-6.24	-6.24

CA SUBSCRIBER PRICE

FILE 'REGISTRY' ENTERED AT 12:01:49 ON 18 APR 2007

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Property values tagged with IC are from the ZIC/VINITI data file provided by InfoChem.

STRUCTURE FILE UPDATES: 16 APR 2007 HIGHEST RN 930395-50-9

DICTIONARY FILE UPDATES: 16 APR 2007 HIGHEST RN 930395-50-9

New CAS Information Use Policies, enter HELP USAGETERMS for details.

TSCA INFORMATION NOW CURRENT THROUGH December 2, 2006

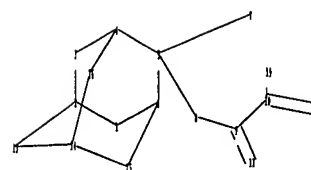
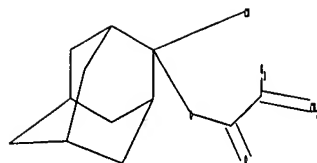
Please note that search-term pricing does apply when conducting SmartSELECT searches.

REGISTRY includes numerically searchable data for experimental and predicted properties as well as tags indicating availability of experimental property data in the original document. For information on property searching in REGISTRY, refer to:

<http://www.cas.org/ONLINE/UG/regprops.html>

=>

Uploading C:\Program Files\Stnexp\Queries\10525429g.str



```

chain nodes :
7  8  9  10  11  12  19
ring nodes :
1  2  3  4  5  6  13  14  15  16
chain bonds :
5-8  5-7  8-9  9-10  9-12  10-11  10-19
ring bonds :
1-2  1-6  2-3  2-13  3-4  4-5  4-16  5-6  6-15  13-14  14-15  14-16
exact/norm bonds :
5-8  8-9  9-12  10-19
exact bonds :
1-2  1-6  2-3  2-13  3-4  4-5  4-16  5-6  5-7  6-15  9-10  10-11  13-14  14-15
14-16
isolated ring systems :
containing 1 :
```

G1:H,CH3,CF3

Match level :

```

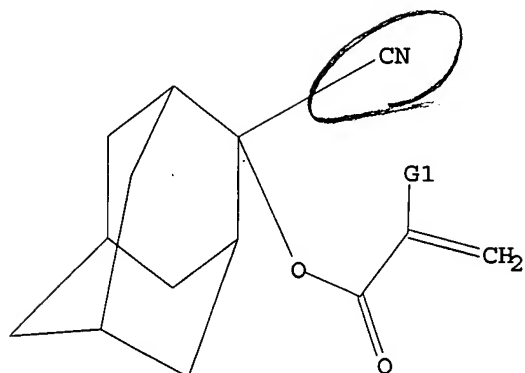
1:Atom  2:Atom  3:Atom  4:Atom  5:Atom  6:Atom  7:CLASS  8:CLASS  9:CLASS  10:CLASS
11:CLASS 12:CLASS 13:Atom 14:Atom 15:Atom 16:Atom 19:CLASS
```

L5 STRUCTURE UPLOADED

=> d 15

L5 HAS NO ANSWERS

L5 STR



G1 H, Me, CF3

Structure attributes must be viewed using STN Express query preparation.

=> s l5

SAMPLE SEARCH INITIATED 12:02:12 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 0 TO ITERATE

100.0% PROCESSED

0 ITERATIONS

0 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**

BATCH **COMPLETE**

PROJECTED ITERATIONS: 0 TO 0

PROJECTED ANSWERS: 0 TO 0

L6 0 SEA SSS SAM L5

=> s l5 sss full

FULL SEARCH INITIATED 12:02:18 FILE 'REGISTRY'

FULL SCREEN SEARCH COMPLETED - 1 TO ITERATE

100.0% PROCESSED

1 ITERATIONS

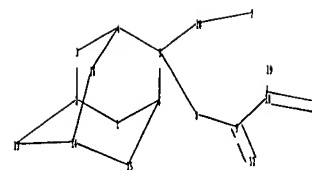
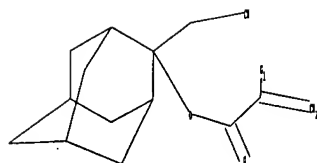
0 ANSWERS

SEARCH TIME: 00.00.01

L7 0 SEA SSS FUL L5

=>

Uploading C:\Program Files\Stnexp\Queries\10525429h.str



```

chain nodes :
7  8  9  10  11  12  19  20
ring nodes :
1  2  3  4  5  6  13  14  15  16
chain bonds :
5-8  5-20  7-20  8-9  9-10  9-12  10-11  10-19
ring bonds :
1-2  1-6  2-3  2-13  3-4  4-5  4-16  5-6  6-15  13-14  14-15  14-16
exact/norm bonds :
5-8  8-9  9-12  10-19
exact bonds :
1-2  1-6  2-3  2-13  3-4  4-5  4-16  5-6  5-20  6-15  7-20  9-10  10-11  13-14
14-15  14-16
isolated ring systems :
containing 1 :

```

G1:H,CH3,CF3

Match level :

```

1:Atom  2:Atom  3:Atom  4:Atom  5:Atom  6:Atom  7:CLASS  8:CLASS  9:CLASS  10:CLASS
11:CLASS 12:CLASS 13:Atom 14:Atom 15:Atom 16:Atom 19:CLASS 20:CLASS

```

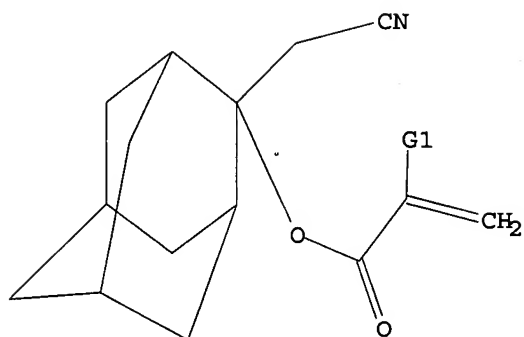
L8 STRUCTURE UPLOADED

=> d l8

L8 HAS NO ANSWERS

L8 STR

10525429f.trn



G1 H, Me, CF3

Structure attributes must be viewed using STN Express query preparation.

=> s l8

SAMPLE SEARCH INITIATED 12:04:02 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 3 TO ITERATE

100.0% PROCESSED 3 ITERATIONS

1 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**

BATCH **COMPLETE**

PROJECTED ITERATIONS: 3 TO 163

PROJECTED ANSWERS: 1 TO 80

L9 1 SEA SSS SAM L8

=> s l8 sss full

FULL SEARCH INITIATED 12:04:08 FILE 'REGISTRY'

FULL SCREEN SEARCH COMPLETED - 91 TO ITERATE

100.0% PROCESSED 91 ITERATIONS

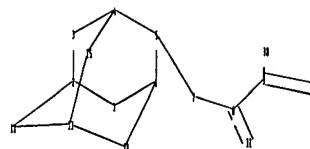
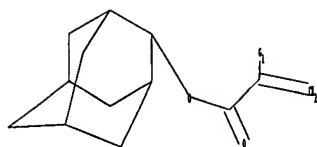
SEARCH TIME: 00.00.01

18 ANSWERS

L10 18 SEA SSS FUL L8

=>

Uploading C:\Program Files\Stnexp\Queries\10525429i.str



```

chain nodes :
7  8  9 10 11 18
ring nodes :
1  2  3  4  5  6 12 13 14 15
chain bonds :
5-7  7-8  8-9  8-11  9-10  9-18
ring bonds :
1-2  1-6  2-3  2-12  3-4  4-5  4-15  5-6  6-14  12-13  13-14  13-15
exact/norm bonds :
5-7  7-8  8-11  9-18
exact bonds :
1-2  1-6  2-3  2-12  3-4  4-5  4-15  5-6  6-14  8-9  9-10  12-13  13-14  13-15
isolated ring systems :
containing 1 :

```

G1:H,CH3,CF3

Match level :

```

1:Atom  2:Atom  3:Atom  4:Atom  5:Atom  6:Atom  7:CLASS  8:CLASS  9:CLASS 10:CLASS
11:CLASS 12:Atom 13:Atom 14:Atom 15:Atom 18:CLASS

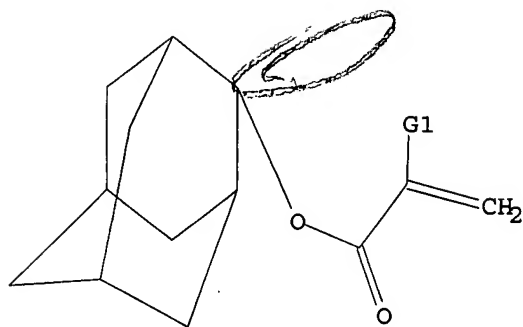
```

L11 STRUCTURE UPLOADED

=> d l11

L11 HAS NO ANSWERS

L11 STR



G1 H, Me, CF3

Structure attributes must be viewed using STN Express query preparation.

=> s l11

SAMPLE SEARCH INITIATED 12:05:15 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 1028 TO ITERATE

100.0% PROCESSED 1028 ITERATIONS

50 ANSWERS

INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
 BATCH **COMPLETE**

PROJECTED ITERATIONS: 18637 TO 22483

PROJECTED ANSWERS: 2072 TO 3486

L12 50 SEA SSS SAM L11

=> s l11 sss full

FULL SEARCH INITIATED 12:05:21 FILE 'REGISTRY'

FULL SCREEN SEARCH COMPLETED - 19689 TO ITERATE

100.0% PROCESSED 19689 ITERATIONS

2434 ANSWERS

SEARCH TIME: 00.00.01

L13 2434 SEA SSS FUL L11

=> FIL HCAPLUS

COST IN U.S. DOLLARS

SINCE FILE	TOTAL
ENTRY	SESSION
517.65	751.16

FULL ESTIMATED COST

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)

SINCE FILE	TOTAL
ENTRY	SESSION
0.00	-6.24

CA SUBSCRIBER PRICE

FILE 'HCAPLUS' ENTERED AT 12:05:26 ON 18 APR 2007

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FILE COVERS 1907 - 18 Apr 2007 VOL 146 ISS 17
FILE LAST UPDATED: 16 Apr 2007 (20070416/ED)

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This file contains CAS Registry Numbers for easy and accurate substance identification.

=> d his

(FILE 'HOME' ENTERED AT 11:54:08 ON 18 APR 2007)

FILE 'REGISTRY' ENTERED AT 11:57:01 ON 18 APR 2007

L1 STRUCTURE UPLOADED
L2 1 S L1
L3 18 S L1 SSS FULL

FILE 'HCAPLUS' ENTERED AT 11:57:32 ON 18 APR 2007

L4 8 S L3

FILE 'REGISTRY' ENTERED AT 12:01:49 ON 18 APR 2007

L5 STRUCTURE UPLOADED
L6 0 S L5
L7 0 S L5 SSS FULL
L8 STRUCTURE UPLOADED
L9 1 S L8
L10 18 S L8 SSS FULL
L11 STRUCTURE UPLOADED
L12 50 S L11
L13 2434 S L11 SSS FULL

FILE 'HCAPLUS' ENTERED AT 12:05:26 ON 18 APR 2007

=> s l10

L14 8 L10

=> s l13

L15 1388 L13

=> s l15 and cyano

82636 CYANO

3 CYANOS

82637 CYANO

(CYANO OR CYANOS)

L16 101 L15 AND CYANO

=> s l16 and adamantane

7252 ADAMANTANE

1119 ADAMANTANES

7543 ADAMANTANE

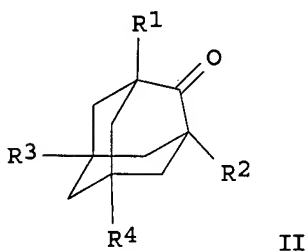
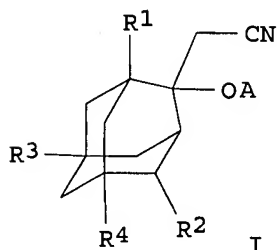
(ADAMANTANE OR ADAMANTANES)

L17 3 L16 AND ADAMANTANE

=> d l14 ibib abs hitstr tot

L14 ANSWER 1 OF 8 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 2006:1030320 HCAPLUS
 DOCUMENT NUMBER: 145:377669
 TITLE: Manufacture of alkali metal 2-cyanomethyl-2-adamantanolates and 2-cyanomethyl-2-adamantyl unsaturated esters
 INVENTOR(S): Maehara, Takayuki
 PATENT ASSIGNEE(S): Tokuyama Corp., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 18pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

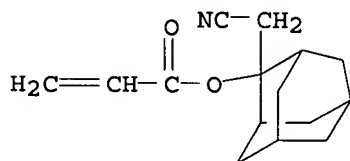
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2006265106	A	2006-10-05	JP 2005-81140	20050322
PRIORITY APPLN. INFO.: GI			JP 2005-81140	20050322



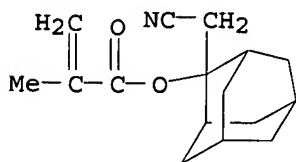
AB The adamantanolates I (R1-R4 = H, C1-5 alkyl; A = alkali metal) are manufactured by treatment of 2-adamantanones II (R1-R4 = same as above) with MeCN and NAR5R6 (R5, R6 = H, C1-5 alkyl; A = alkali metal). The esters are useful for resists. Thus, (iso-Pr)₂NH was treated with BuLi in THF, treated with 2-adamantanone (III) and MeCN to give a solution containing a reaction mixture containing Li 2-cyanomethyl-2-adamantanolate (IV) 90, III 7, and 2-cyanomethyleneadamantane (V) 3%. The solution was dropped into a THF solution containing methacrylic anhydride to give an oil containing III 7, IV 18, V 8, and 2-cyanomethyl-2-adamantyl methacrylate 67%.

IT 875924-12-2P
 RL: IMF (Industrial manufacture); PREP (Preparation)
 (manufacture of (cyanomethyl)adamantyl unsatd. esters for resists from adamantanones via alkali metal (cyanomethyl)adamantanolates)

RN 875924-12-2 HCAPLUS
 CN 2-Propenoic acid, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester (9CI)
 (CA INDEX NAME)



IT 853644-75-4P, 2-Cyanomethyl-2-adamantyl methacrylate
 RL: IMF (Industrial manufacture); PUR (Purification or recovery); PREP (Preparation)
 (manufacture of (cyanomethyl)adamantyl unsatd. esters for resists from adamantanones via alkali metal (cyanomethyl)adamantanolates)
 RN 853644-75-4 HCAPLUS
 .CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester (9CI) (CA INDEX NAME)



L14 ANSWER 2 OF 8 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 2006:941254 HCAPLUS
 DOCUMENT NUMBER: 145:324980
 TITLE: Deep-UV or electron-beam lithography, resists and polymers therefor, and manufacture thereof
 INVENTOR(S): Momose, Akira; Ueda, Shoji
 PATENT ASSIGNEE(S): Mitsubishi Rayon Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 76pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2006241233	A	20060914	JP 2005-56078	20050301
PRIORITY APPLN. INFO.:			JP 2005-56078	20050301

AB The polymers have repeating units containing acid-leaving groups formed from polymerization of monomers J(XSH)_n [X = single bond, B11, SB11, OSiB13B14 (B11

= C1-20 hydrocarbylene; B12 = H, C1-10 alkyl; B13, B14 = H, C1-10 alkyl); n = 3-24; J = n-valent hydrocarbon] in the presence of initiators. Resists containing the polymers are applied on substrates, exposed to ≤250-nm light, and developed to form patterns with small line edge roughness.

IT 909100-43-2P
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (deep-UV or electron-beam resists containing starburst polymers having acid-leaving groups)

RN 909100-43-2 HCAPLUS

CN Bicyclo[2.2.1]heptane-2-carboxylic acid, 5(or 6)-[(2-methyl-1-oxo-2-

10525429f.trn

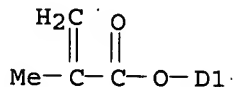
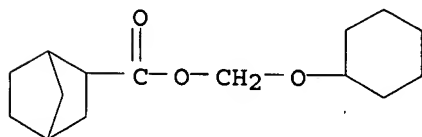
propenyl)oxy]-, (cyclohexyloxy)methyl ester, polymer with
2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate and
tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 870136-27-9

CMF C19 H28 O5

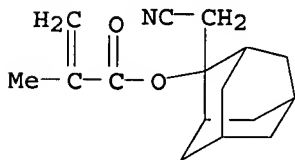
CCI IDS



CM 2

CRN 853644-75-4

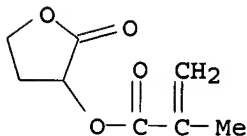
CMF C16 H21 N O2



CM 3

CRN 195000-66-9

CMF C8 H10 O4



L14 ANSWER 3 OF 8 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2006:141410 HCAPLUS

DOCUMENT NUMBER: 144:213169

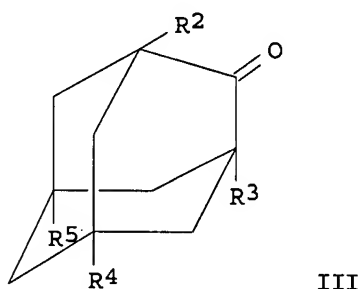
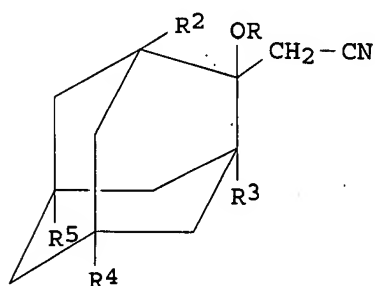
TITLE: Preparation of 2-cyanomethyl-2-adamantyl esters and
their intermediates

INVENTOR(S): Maehara, Takayuki

PATENT ASSIGNEE(S): Tokuyama Corp., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 21 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2006045161	A	20060216	JP 2004-231406	20040806
PRIORITY APPLN. INFO.:			JP 2004-231406	20040806
OTHER SOURCE(S):	MARPAT	144:213169		

GI



AB The esters [R = COR1; R1 = (un)substituted polymerizable unsatd. hydrocarbyl; R2-R5 = H, C1-5 alkyl], useful as monomers for functional materials and electronic materials, are prepared by reacting I (R = H, alkali metal; R2-R5 = same as above) (II) with polymerizable unsatd. carboxylic anhydrides or halides. II (R = H) are prepared by reacting 2-adamantanones III (R2-R5 = same as above) with MeCN in the presence of alkali metals and hydrolyzing the resulting II (R = alkali metal). Thus, Li was added to a mixture of 2-adamantanone, MeCN, and THF in 3 portions and the reaction mixture was stirred at 45° for 5 h. The reaction solution containing Li 2-cyanomethyl-2-adamantanolate was added dropwise to a mixture of methacrylic anhydride and THF at ≤10° and the reaction mixture was stirred for 1 h to give 2-cyanomethyl-2-adamantyl methacrylate with purity 92%.

IT 853644-75-4P, 2-Cyanomethyl-2-adamantyl methacrylate
 875924-12-2P

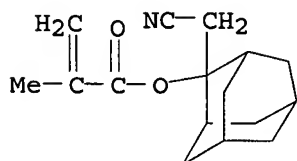
RL: IMF (Industrial manufacture); PUR (Purification or recovery); SPN (Synthetic preparation); PREP (Preparation)
 (preparation of polymerizable (cyanomethyl)adamantyl esters by addition of

MeCN

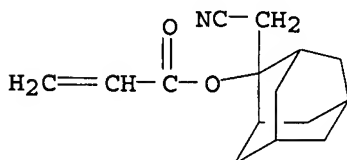
to adamantanones using alkali metals, hydrolysis of alcoholates, and esterification)

RN 853644-75-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester (9CI) (CA INDEX NAME)



RN 875924-12-2 HCAPLUS
 CN 2-Propenoic acid, 2-(cyanomethyl)tricyclo[3.3.1.1.3,7]dec-2-yl ester (9CI)
 (CA INDEX NAME)



L14 ANSWER 4 OF 8 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2006:75721 HCAPLUS

DOCUMENT NUMBER: 144:160277

TITLE: Photoresists, cyano-substituted (meth)acrylate polymers therefor, their monomers, and synthesis thereof

INVENTOR(S): Shimizu, Shigeru

PATENT ASSIGNEE(S): Mitsubishi Rayon Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 16 pp.

CODEN: JKXXAF

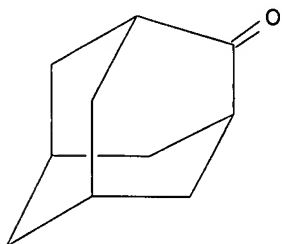
DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2006022165	A	20060126	JP 2004-199767	20040706
PRIORITY APPLN. INFO.: GI			JP 2004-199767	20040706



I

AB Carbonyl compds. I are reacted with malondinitrile in the presence of bases and then with (meth)acrylic acid derivs. to afford esters represented by H₂C:CRCO₂G (G = Q1-Q10; R = H, Me). Polymers of the esters

and photoresists containing the polymers are further claimed. The polymers exhibit good adhesion to substrates, dry etching resistance, and high sensitivity.

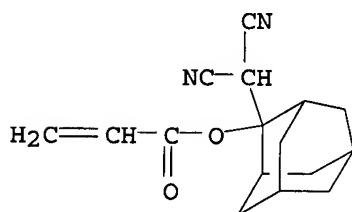
IT 873805-99-3P 873806-00-9P 873806-09-8P
873806-10-1P

RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)

(monomers; synthesis of (meth)acrylates having cyano-substituted alicyclic groups for pos. photoresists)

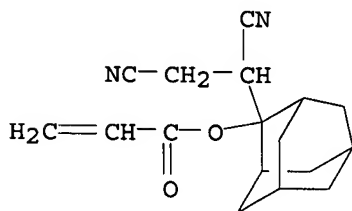
RN 873805-99-3 HCAPLUS

CN 2-Propenoic acid, 2-(dicyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester (9CI) (CA INDEX NAME)



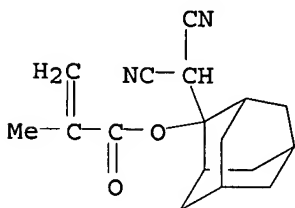
RN 873806-00-9 HCAPLUS

CN 2-Propenoic acid, 2-(1,2-dicyanoethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester (9CI) (CA INDEX NAME)



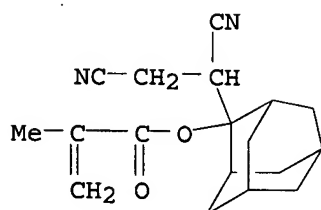
RN 873806-09-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(dicyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester (9CI) (CA INDEX NAME)



RN 873806-10-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(1,2-dicyanoethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester (9CI) (CA INDEX NAME)



IT 873806-76-9P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(resist components; synthesis of (meth)acrylates having cyano-substituted alicyclic groups for pos. photoresists)

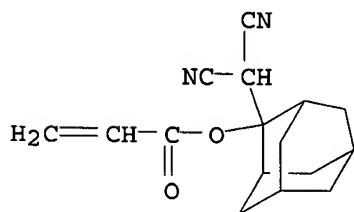
RN 873806-76-9 HCAPLUS

CN 2-Propenoic acid, 2-(dicyanomethyl)tricyclo[3.3.1.13,7]dec-2-yl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 873805-99-3

CMF C16 H18 N2 O2



L14 ANSWER 5 OF 8 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2005:1154518 HCAPLUS

DOCUMENT NUMBER: 143:422757

TITLE: Adamantane derivative and process for producing the same

INVENTOR(S): Ito, Hajime; Tanaka, Shinji

PATENT ASSIGNEE(S): Idemitsu Kosan Co., Ltd., Japan

SOURCE: PCT Int. Appl., 20 pp.

CODEN: PIXXD2

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

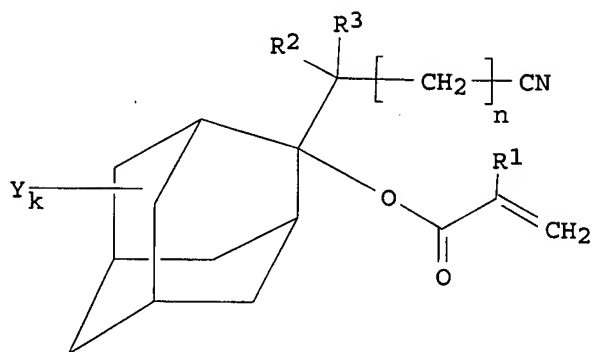
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2005100304	A1	20051027	WO 2004-JP14835	20041007
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW				

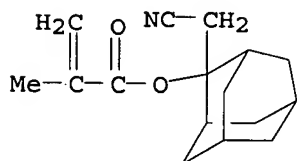
RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM,
 AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK,
 EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE,
 SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE,
 SN, TD, TG

CN 1780812	A	20060531	CN 2004-80000851	20041007
EP 1731504	A1	20061213	EP 2004-792132	20041007
R: BE, DE, FR, GB				
US 2006167302	A1	20060727	US 2005-525429	20050223
JP 2005314383	A	20051110	JP 2005-92620	20050328
PRIORITY APPLN. INFO.:			JP 2004-109743	A 20040402
			WO 2004-JP14835	W 20041007

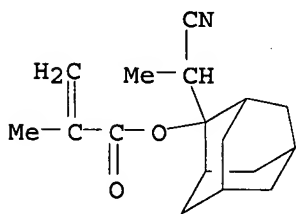
OTHER SOURCE(S): MARPAT 143:422757
 GI



- AB Title adamantane derivative is characterized by having a structure represented by the general formula (I): wherein R1 is H, Me, or trifluoromethyl; Y is C1-C10 alkyl, halogen, H, or =O (2 groups of Y); R2 and R3 are H or, C1-C10 alkyl, k is 0-14; and n is 0-3. The process for producing the adamantane derivative I with n is 0 (e.g., 2-cyanomethyl-2-adamantyl methacrylate) comprises reacting an adamantanone compound (e.g., adamantanone) with a nitrile compound (e.g., acetonitrile) and then with an acid halide or acid anhydride of a (meth)acrylic acid compound (e.g., methacrylic anhydride). The adamantane derivative I is a novel adamantane derivative useful as a monomer for a functional resin such as a photosensitive resin for use in the field of photolithog. It can be efficiently produced by the process.
- IT 853644-75-4P, 2-Cyanomethyl-2-adamantyl methacrylate
 868135-90-4P, 2-(1-Cyanoethyl)-2-adamantyl methacrylate
 RL: IMF (Industrial manufacture); PRP (Properties); PREP (Preparation)
 (production of adamantane derivative as monomer for photosensitive resin for use in the field of photolithog.)
- RN 853644-75-4 HCAPLUS
- CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester (9CI) (CA INDEX NAME)



RN 868135-90-4 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-(1-cyanoethyl)tricyclo[3.3.1.1.3]dec-2-yl ester (9CI) (CA INDEX NAME)



REFERENCE COUNT: 2 THERE ARE 2 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L14 ANSWER 6 OF 8 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 2005:1026891 HCAPLUS
 DOCUMENT NUMBER: 143:336279
 TITLE: Aromatic-free and fluorine-free photoresists and photoacid generators containing pendant cyanoadamantyl methacrylate polymers
 INVENTOR(S): Bae, Young C.; Kavanagh, Robert J.
 PATENT ASSIGNEE(S): Rohm and Haas Electronic Materials, L.L.C., USA
 SOURCE: PCT Int. Appl., 43 pp.
 CODEN: PIXXD2
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 2
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2005086901	A2	20050922	WO 2005-US7910	20050308
WO 2005086901	A3	20061026		
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW				
RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
EP 1586944	A1	20051019	EP 2005-251340	20050307
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK,				

BA, HR, IS, YU

US 2005208418	A1	20050922	US 2005-75545	20050308
JP 2005281307	A	20051013	JP 2005-63253	20050308
KR 2006043495	A	20060515	KR 2005-18985	20050308
CN 1670014	A	20050921	CN 2005-10054530	20050309

PRIORITY APPLN. INFO.:

US 2004-551448P	P	20040308
US 2004-551880P	P	20040309

AB Aromatic group-free and fluorine-free photoresist compns. containing ≥ 1 photoacid generator compds. and a resin component, in which the resin component consists of a polymer that contains a cyanoadamantyl group consisting of a cyano group, preferably pendant at the 2- or 4-position of an adamantyl group. Preferred polymers are used in photoresists imaged at wavelengths < 250 nm, especially 193-248 nm.

IT 853644-80-1P 865346-06-1P 865346-07-2P
865346-08-3P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(photoresist; aromatic-free and fluorine-free photoresists and photoacid generators containing pendant cyanoadamantyl methacrylate polymers)

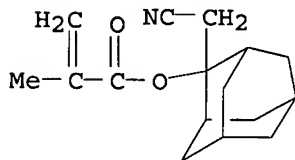
RN 853644-80-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester, polymer with 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 853644-75-4

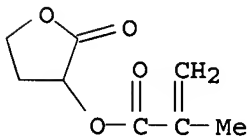
CMF C16 H21 N O2



CM 2

CRN 195000-66-9

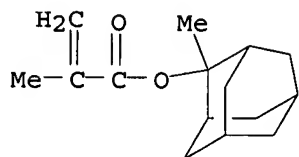
CMF C8 H10 O4



CM 3

CRN 177080-67-0

CMF C15 H22 O2



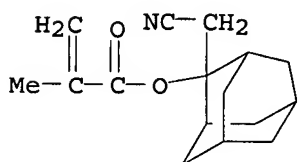
RN 865346-06-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.13,7]dec-2-yl ester, polymer with 1-ethylcyclopentyl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 853644-75-4

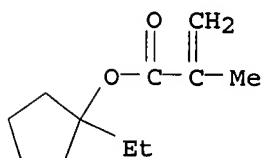
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CM 2

CRN 266308-58-1

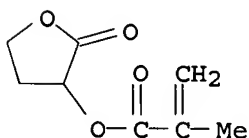
CMF C11 H18 O2



CM 3

CRN 195000-66-9

CMF C8 H10 O4



RN 865346-07-2 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.13,7]dec-2-yl ester, polymer with 2-ethyltricyclo[3.3.1.13,7]dec-2-yl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate

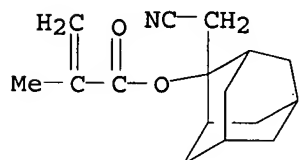
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(9CI) (CA INDEX NAME)

CM 1

CRN 853644-75-4

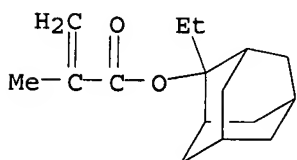
CMF C16 H21 N O2



CM 2

CRN 209982-56-9

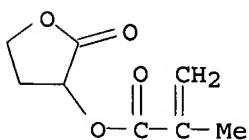
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CM 3

CRN 195000-66-9

CMF C8 H10 O4



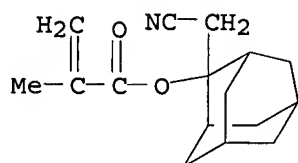
RN 865346-08-3 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with bicyclo[2.2.1]hept-2-ene, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate and 1-ethylcyclopentyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 853644-75-4

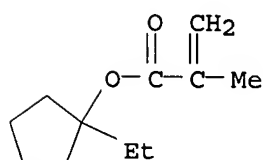
CMF C16 H21 N O2



CM 2

CRN 266308-58-1

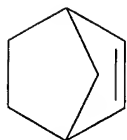
CMF C11 H18 O2



CM 3

CRN 498-66-8

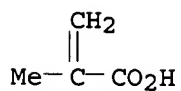
CMF C7 H10



CM 4

CRN 79-41-4

CMF C4 H6 O2



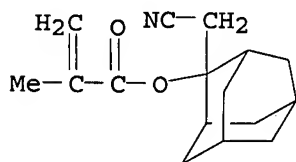
IT 853644-75-4P

RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)

(synthesis and polymerization of; aromatic-free and fluorine-free photoresists and photoacid generators containing pendant cyanoadamantyl methacrylate polymers)

RN 853644-75-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1.3]dec-2-yl ester (9CI) (CA INDEX NAME)



L14 ANSWER 7 OF 8 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2005:998776 HCAPLUS

DOCUMENT NUMBER: 143:295593

TITLE: Photoresists comprising cyano adamantyl moiety-containing polymers

INVENTOR(S): Bae, Young C.; Kananagh, Robert J.

PATENT ASSIGNEE(S): Rohm and Haas Electronic Materials, L.L.C., USA

SOURCE: Eur. Pat. Appl., 21 pp.

CODEN: EPXXDW

DOCUMENT TYPE: Patent

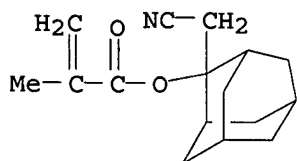
LANGUAGE: English

FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1574903	A1	20050914	EP 2005-251342	20050307
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, BA, HR, IS, YU				
JP 2005258438	A	20050922	JP 2005-61914	20050307
US 2005208417	A1	20050922	US 2005-75544	20050308
CN 1683997	A	20051019	CN 2005-10054399	20050308
KR 2006043494	A	20060515	KR 2005-18984	20050308
PRIORITY APPLN. INFO.:			US 2004-551448P	P 20040308
AB Cyano adamantyl compds., polymers that comprise polymerized units of such compds., and photoresist compns. that comprise such polymers are provided. Preferred polymers of the invention are employed in photoresists imaged at wavelengths less than 250 nm such as 248 nm and 193 nm.				
IT 864367-15-7P 864367-16-8P				
RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)				
(preparation of cyano adamantyl moiety-containing polymers for photoresists)				
RN 864367-15-7 HCAPLUS				
CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1 ^{3,7}]dec-2-yl ester, polymer with 3-hydroxytricyclo[3.3.1.1 ^{3,7}]dec-1-yl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)				
CM 1				
CRN 853644-75-4				
CMF C16 H21 N O2				

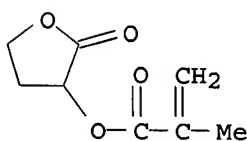
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CM 2

CRN 195000-66-9

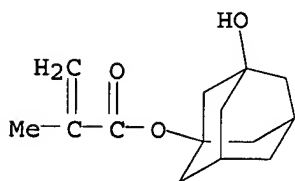
CMF C8 H10 O4



CM 3

CRN 115372-36-6

CMF C14 H20 O3



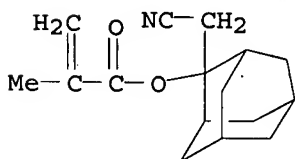
RN 864367-16-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 5-cyanobicyclo[2.2.1]hept-2-yl ester, polymer with 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

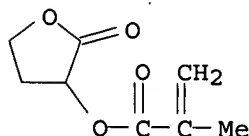
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CMF C16 H21 N O2



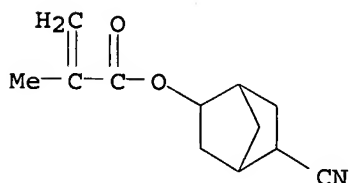
CM 2

CRN 195000-66-9
CMF C8 H10 O4

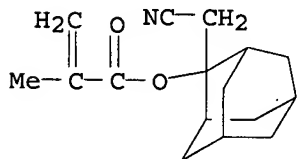


CM 3

CRN 123118-84-3
CMF C12 H15 N O2



IT 853644-75-4P
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
(preparation of cyano adamantyl moiety-containing polymers for photoresists)
RN 853644-75-4 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.3,7]dec-2-yl ester (9CI) (CA INDEX NAME)



REFERENCE COUNT: 2 THERE ARE 2 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L14 ANSWER 8 OF 8 HCAPLUS COPYRIGHT 2007 ACS on STN
ACCESSION NUMBER: 2005:522122 HCAPLUS
DOCUMENT NUMBER: 143:44193
TITLE: Preparation of (meth)acrylates and their raw materials for polymers with good sensitivity, resolution, and dry etching resistance.
INVENTOR(S): Otake, Atsushi
PATENT ASSIGNEE(S): Mitsubishi Rayon Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 42 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

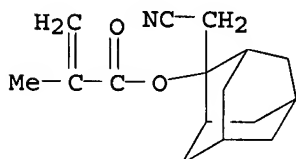
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005154427	A	20050616	JP 2004-314525	20041028
PRIORITY APPLN. INFO.:			JP 2003-372356	A 20031031

AB The present invention relates to β -cyanohydrin analogs CR1R2(OX)CN, wherein X = H, alkali metal, or magnesium halide; R1 = C1-6 alkyl having (alkyl substituted) C4-16 cyclic hydrocarbon group; R2 = C1-6 alkyl (R1 and R2 form (alkyl substituted) C4-16 cyclo hydrocarbon group by bonding carbon atoms); and the alkyl and cyclic hydrocarbon groups may be substituted with hydroxy, carboxy, C1-6 alkoxy or acyl, or carboxy group esterified with C1-6 alcs. Thus, 2.05 g acetonitrile and 7.6 g camphor were reacted at 0° in the presence of butyllithium, 5.2 h methacryloyl chloride was added therein at -40° and reacted at -40° for 2 h to give a cyano-containing methacrylate, 52.2 parts of which was copolymerized with 93.7 parts 2-methacryloyloxy-2-methyladamantane and 68.1 parts α -methacryloyloxy- γ -butyrolactone in the presence of AIBN to give a copolymer with Mw 7600, polydispersity 1.75, good sensitivity, resolution, and dry etching resistance when used as a photoresist material.

IT 853644-75-4P
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(monomer; preparation of (meth)acrylates and their raw materials for polymers with good sensitivity, resolution, and dry etching resistance.)

RN 853644-75-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester (9CI) (CA INDEX NAME)



IT 853644-80-1P 853644-83-4P 853735-28-1P
RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(preparation of (meth)acrylates and their raw materials for polymers with good sensitivity, resolution, and dry etching resistance.)

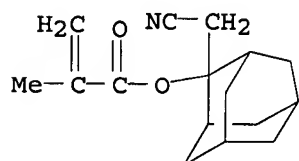
RN 853644-80-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester, polymer with 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 853644-75-4

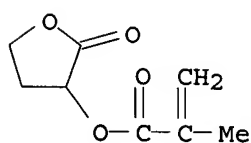
CMF C16 H21 N O2



CM 2

CRN 195000-66-9

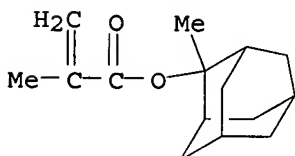
CMF C8 H10 O4



CM 3

CRN 177080-67-0

CMF C15 H22 O2



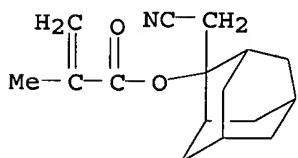
RN 853644-83-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.13,7]dec-2-yl ester, polymer with 1-methylcyclohexyl 2-methyl-2-propenoate, octahydro-1(or 3)-oxo-4,7-methanoisobenzofuran-5-yl 2-methyl-2-propenoate and tricyclo[3.3.1.13,7]dec-1-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 853644-75-4

CMF C16 H21 N O2



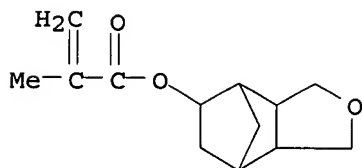
10525429f.trn

CM 2

CRN 436852-34-5

CMF C13 H16 O4

CCI IDS

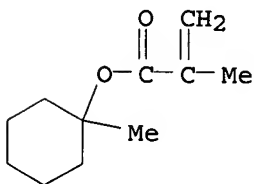


D2=O

CM 3

CRN 76392-14-8

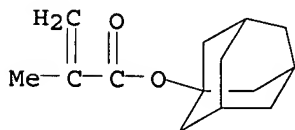
CMF C11 H18 O2



CM 4

CRN 16887-36-8

CMF C14 H20 O2



RN 853735-28-1 HCAPLUS

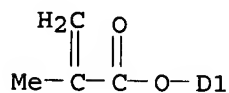
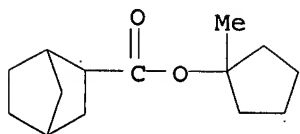
CN Bicyclo[2.2.1]heptane-2-carboxylic acid, 5(or 6)-[(2-methyl-1-oxo-2-propenyl)oxy]-, 1-methylcyclopentyl ester, polymer with 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 853735-27-0

CMF C18 H26 O4

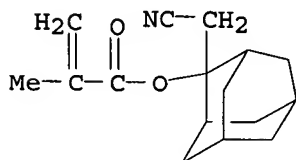
CCI IDS



CM 2

CRN 853644-75-4

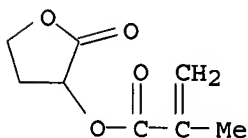
CMF C16 H21 N O2



CM 3

CRN 195000-66-9

CMF C8 H10 O4



IT 853644-77-6P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(preparation of (meth)acrylates and their raw materials for polymers with good sensitivity, resolution, and dry etching resistance.)

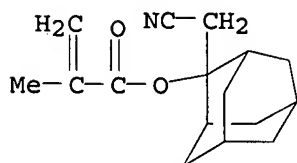
RN 853644-77-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 853644-75-4

CMF C16 H21 N O2



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L17 ANSWER 1 OF 3 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2005:998776 HCAPLUS

DOCUMENT NUMBER: 143:295593

TITLE: Photoresists comprising cyano adamantyl moiety-containing polymers

INVENTOR(S): Bae, Young C.; Kananagh, Robert J.

PATENT ASSIGNEE(S): Rohm and Haas Electronic Materials, L.L.C., USA

SOURCE: Eur. Pat. Appl., 21 pp.

CODEN: EPXXDW

DOCUMENT TYPE: Patent

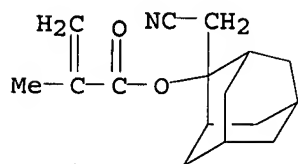
LANGUAGE: English

FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1574903	A1	20050914	EP 2005-251342	20050307
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, BA, HR, IS, YU				
JP 2005258438	A	20050922	JP 2005-61914	20050307
US 2005208417	A1	20050922	US 2005-75544	20050308
CN 1683997	A	20051019	CN 2005-10054399	20050308
KR 2006043494	A	20060515	KR 2005-18984	20050308
PRIORITY APPLN. INFO.:			US 2004-551448P	P 20040308
AB Cyano adamantyl compds., polymers that comprise polymerized units of such compds., and photoresist compns. that comprise such polymers are provided. Preferred polymers of the invention are employed in photoresists imaged at wavelengths less than 250 nm such as 248 nm and 193 nm.				
IT 864367-15-7P 864367-16-8P				
RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (preparation of cyano adamantyl moiety-containing polymers for photoresists)				
RN 864367-15-7 HCAPLUS				
CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.1 ^{3,7}]dec-2-yl ester, polymer with 3-hydroxytricyclo[3.3.1.1 ^{3,7}]dec-1-yl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)				
CM 1				
CRN 853644-75-4				
CMF C16 H21 N O2				

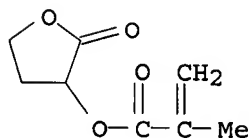
10525429f.trn



CM 2

CRN 195000-66-9

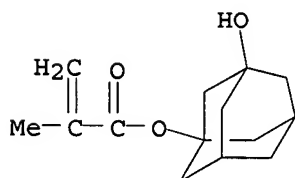
CMF C8 H10 O4



CM 3

CRN 115372-36-6

CMF C14 H20 O3



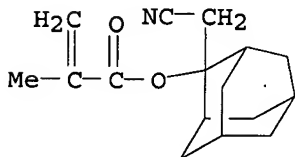
RN 864367-16-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 5-cyanobicyclo[2.2.1]hept-2-yl ester, polymer with 2-(cyanomethyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 853644-75-4

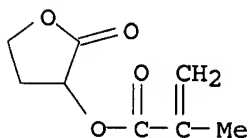
CMF C16 H21 N O2



CM 2

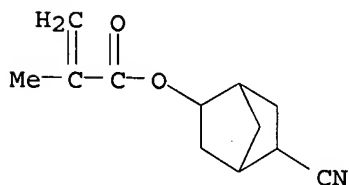
10525429f.trn

CRN 195000-66-9
CMF C8 H10 O4

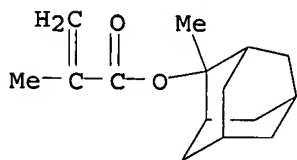


CM 3

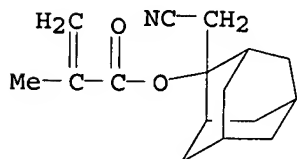
CRN 123118-84-3
CMF C12 H15 N O2



IT 177080-67-0P 853644-75-4P
RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT
(Reactant or reagent)
(preparation of cyano adamantyl moiety-containing polymers for
photoresists)
RN 177080-67-0 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.13,7]dec-2-yl ester
(CA INDEX NAME)



RN 853644-75-4 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 2-(cyanomethyl)tricyclo[3.3.1.13,7]dec-2-yl
ester (9CI) (CA INDEX NAME)



REFERENCE COUNT: 2 THERE ARE 2 CITED REFERENCES AVAILABLE FOR THIS
RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L17 ANSWER 2 OF 3 HCAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2004:447253 HCAPLUS

DOCUMENT NUMBER: 141:31078

TITLE: Positive-working resists with good F2 excimer laser transparency

INVENTOR(S): Kanna, Shinichi; Mizutani, Kazuyoshi; Sasaki, Tomoya

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 77 pp.

CODEN: JKXXAF

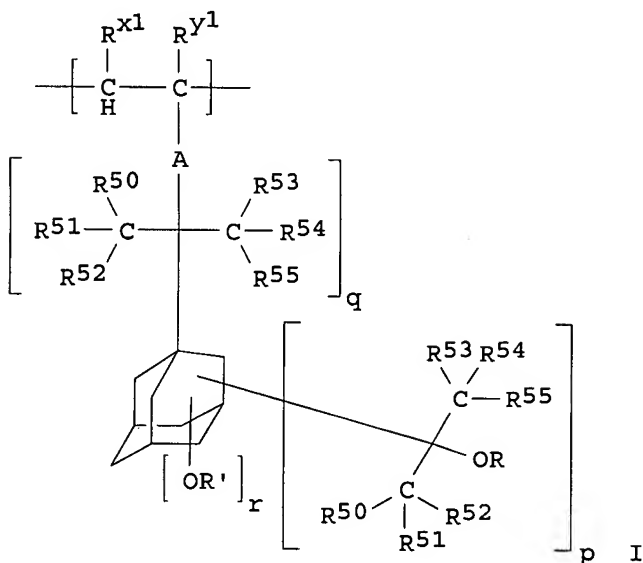
DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004157321	A	20040603	JP 2002-322832	20021106
PRIORITY APPLN. INFO.: GI			JP 2002-322832	20021106



AB The resists contain resins having structural repeating units I (R_{x1} , R_{y1} = H, halo, cyano, alkyl; R_{50} - R_{55} = H, F, alkyl; ≥ 1 of R_{50} - R_{55} = F or fluoroalkyl; R, R' = H, organic group; A = O, OR600; R60 = alkylene; $p = 0-3$; p , $r = 0, 1$; $p + q \geq 1$) and increasing solubility in aqueous alkaline solns. by treatment with acids, photoacid generators, and solvents. The resists suppress development defects.

IT 697748-24-6P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(pos.-working resists containing polymers bearing adamantyl groups and showing good F2 excimer laser transparency)

RN 697748-24-6 HCAPLUS

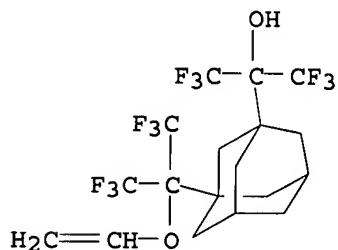
CN 2-Propenoic acid, 2-(trifluoromethyl)-, 2-methyltricyclo[3.3.1.1.3]dec-2-yl ester, polymer with 3-[1-(ethenyloxy)-2,2,2-trifluoro-1-(trifluoromethyl)ethyl]- α, α -bis(trifluoromethyl)tricyclo[3.3.1

.13,7]decane-1-methanol (9CI) (CA INDEX NAME)

CM 1

CRN 676515-92-7

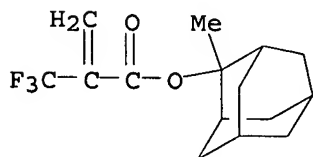
CMF C18 H18 F12 O2



CM 2

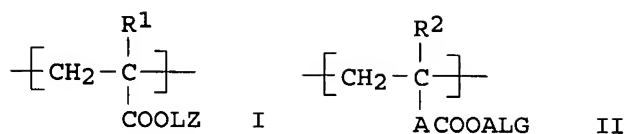
CRN 188739-86-8

CMF C15 H19 F3 O2



L17 ANSWER 3 OF 3 HCAPLUS COPYRIGHT 2007 ACS on STN
 ACCESSION NUMBER: 2004:430044 HCAPLUS
 DOCUMENT NUMBER: 140:414953
 TITLE: Chemically amplified positive-working far-UV photoresist compositions
 INVENTOR(S): Sato, Kenichiro; Kodama, Kunihiro
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 75 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004151355	A	20040527	JP 2002-316284	20021030
PRIORITY APPLN. INFO.:			JP 2002-316284	20021030
OTHER SOURCE(S):	MARPAT	140:414953		
GI				



AB The compns. contain polymers increasing solubility rate in alkaline developers upon

acid action and containing repeating units of A1-3 including [A1; CH₂C(R₁)(CO₂LZ)] [R₁ = H, alkyl; L = single bond, alkylene, ether, ester, etc.; Z = CO₂H, OH, SO₂N(R₃)₂, COCH₂COR₄, etc.; R₃, R₅-7 = H, alkyl; R₄ = hydrocarbyl; m = 1-20; Z = [CH(R₅)CH(R₆)O]_mR₇ when L = single bond], [A₂; CH₂C(R₂)(ACO₂ALG)] [R₂ = H, Me; A = single bond, connecting group; ALG = Q, etc.; R₁₁ = Me, Et, Pr, etc.; Z = atomic group forming alicyclic hydrocarbylene group with carbon], and [A₃; CH₂C(R₃)(A'Z₃(OH)p)] [R₃ = H, Me; A' = single bond, divalent connecting group; Z₃ = alicyclic hydrocarbylene having valences of (p + 1); p = 1-3]; sulfonate enone photoacid generator I or II [RB₁-B₃ = H, alkyl, alkenyl, etc.; RB₄-B₅ = H, cyano, alkyl, etc.; Y₁-2 = alkyl, aryl, aralkyl, etc.; n = 1-4; ≥2 selected from RB₁-B₅ and Y₁-2 may form a ring; ≥2 selected from RB₁-B₅ and Y₁-2 may be bonded to via a connecting group so as to have ≥2 structure of I and/or II; X- = nonnucleophilic anion]; and solvents. The polymers may further contain repeating units of cyclohexanelactone, norbornane lactone, or adamantane lactone. The compns. provide sharp line edge patterns.

IT 680223-08-9 680223-10-3 680223-12-5
690663-95-7 690663-96-8 690664-16-5

RL: TEM (Technical or engineered material use); USES (Uses)
(in chemical amplified pos.-working far-UV photoresist compns. containing sulfonate enone photoacid generators)

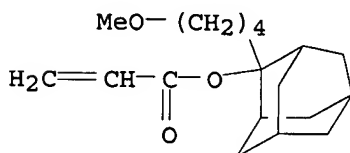
RN 680223-08-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3,5-dihydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl ester, polymer with hexahydro-2-oxo-3,5-methano-2H-cyclopenta[b]furan-6-yl 2-methyl-2-propenoate, 2-(4-methoxybutyl)tricyclo[3.3.1.1^{3,7}]dec-2-yl 2-propenoate, 2-(2-methoxyethoxy)ethyl 2-methyl-2-propenoate and 1-methyl-1-tricyclo[3.3.1.1^{3,7}]dec-1-ylethyl 2-methyl-2-propenoate (9CI)
(CA INDEX NAME)

CM 1

CRN 581784-05-6

CMF C18 H28 O3

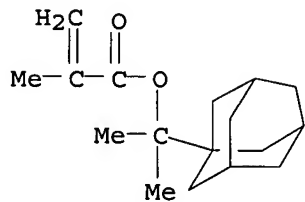


CM 2

CRN 279218-76-7

CMF C17 H26 O2

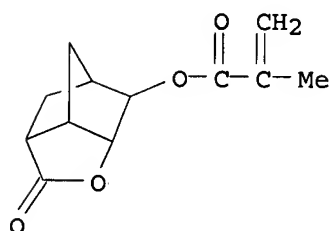
10525429f.trn



CM 3

CRN 254900-07-7

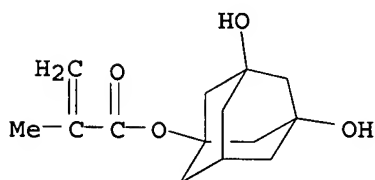
CMF C12 H14 O4



CM 4

CRN 115522-15-1

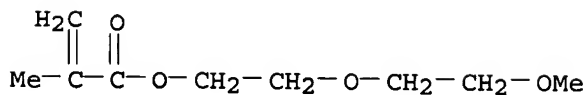
CMF C14 H20 O4



CM 5

CRN 45103-58-0

CMF C9 H16 O4



RN 680223-10-3 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[2-[2-(2-hydroxyethoxy)ethoxy]ethoxy]ethyl ester, polymer with 3-hydroxytricyclo[3.3.1.3.3]dec-1-yl 2-methyl-2-propenoate, 2-methyltricyclo[3.3.1.3.3]dec-2-yl

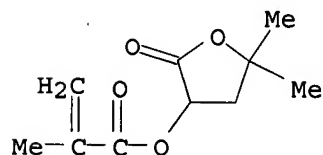
10525429f.trn

2-methyl-2-propenoate and tetrahydro-5,5-dimethyl-2-oxo-3-furanyl
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 280552-09-2

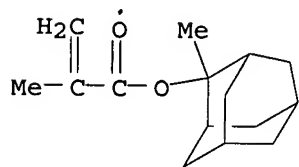
CMF C10 H14 O4



CM 2

CRN 177080-67-0

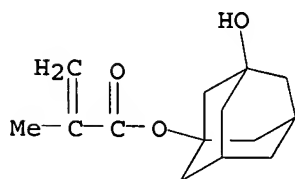
CMF C15 H22 O2



CM 3

CRN 115372-36-6

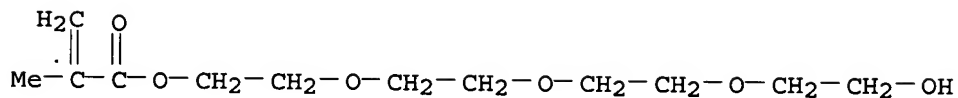
CMF C14 H20 O3



CM 4

CRN 21217-75-4

CMF C12 H22 O6



10525429f.trn

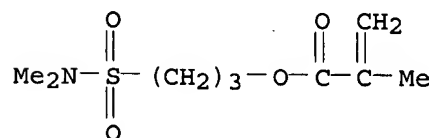
RN 680223-12-5 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-[(dimethylamino)sulfonyl]propyl ester, polymer with 2-ethyltricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate, 3-hydroxy-5,7-dimethyltricyclo[3.3.1.1^{3,7}]dec-1-yl 2-methyl-2-propenoate and tetrahydro-5-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 680223-11-4

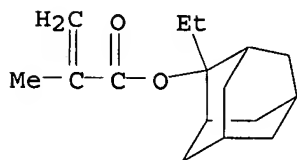
CMF C9 H17 N O4 S



CM 2

CRN 209982-56-9

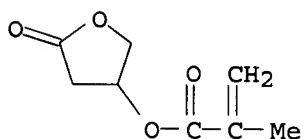
CMF C16 H24 O2



CM 3

CRN 130224-95-2

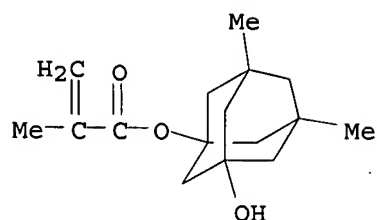
CMF C8 H10 O4



CM 4

CRN 115522-17-3

CMF C16 H24 O3



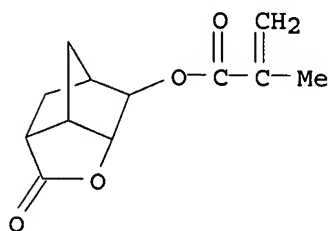
RN 690663-95-7 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, hexahydro-2-oxo-3,5-methano-2H-cyclopenta[b]furan-6-yl ester, polymer with α -(2-methyl-1-oxo-2-propenyl)- ω -hydroxypoly(oxy-1,2-ethanediyl), 2-methyltricyclo[3.3.1.1.3,7]dec-2-yl 2-methyl-2-propenoate and 3,5,7-trihydroxytricyclo[3.3.1.1.3,7]dec-1-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 254900-07-7

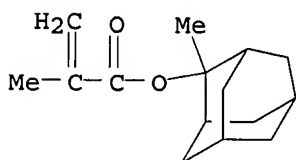
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CM 2

CRN 177080-67-0

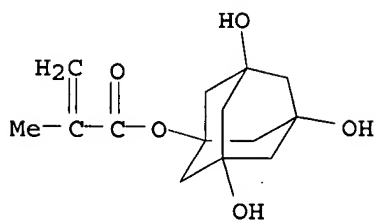
CMF C15 H22 O2



CM 3

CRN 115522-16-2

CMF C14 H20 O5

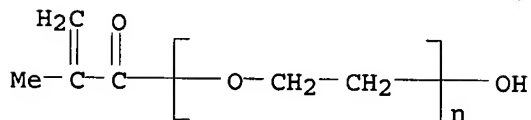


CM 4

CRN 25736-86-1

CMF (C2 H4 O)_n C4 H6 O2

CCI PMS



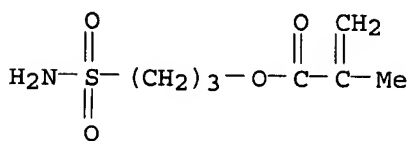
RN 690663-96-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-(aminosulfonyl)propyl ester, polymer with 3,5-dihydroxytricyclo[3.3.1.1.3,7]dec-1-yl 2-methyl-2-propenoate, 2-ethyltricyclo[3.3.1.1.3,7]dec-2-yl 2-methyl-2-propenoate and 7-oxo-6-oxabicyclo[3.2.1]oct-4-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 483364-49-4

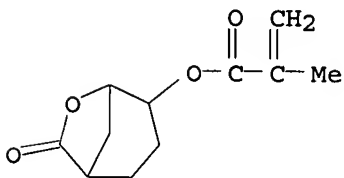
CMF C7 H13 N O4 S



CM 2

CRN 335163-70-7

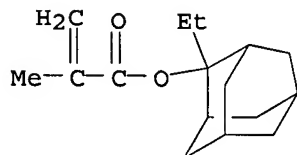
CMF C11 H14 O4



CM 3

CRN 209982-56-9

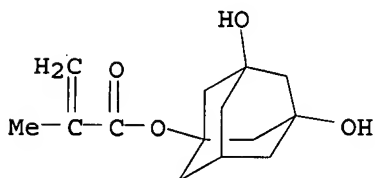
CMF C16 H24 O2



CM 4

CRN 115522-15-1

CMF C14 H20 O4



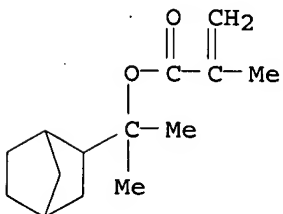
RN 690664-16-5 HCAPLUS

CN Butanedioic acid, mono[1-methyl-2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester, polymer with 1-bicyclo[2.2.1]hept-2-yl-1-methylethyl 2-methyl-2-propenoate, 3,5-dihydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl 2-methyl-2-propenoate, hexahydro-2-oxo-3,5-methano-2H-cyclopenta[b]furan-6-yl 2-propenoate and 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 342014-18-0

CMF C14 H22 O2

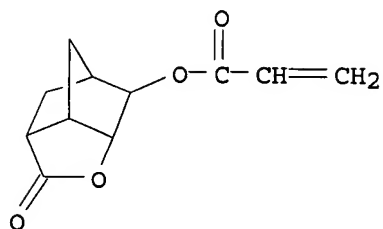


CM 2

CRN 242129-35-7

10525429f.trn

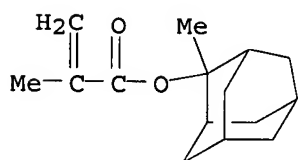
CMF C11 H12 O4



CM 3

CRN 177080-67-0

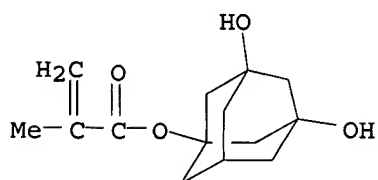
CMF C15 H22 O2



CM 4

CRN 115522-15-1

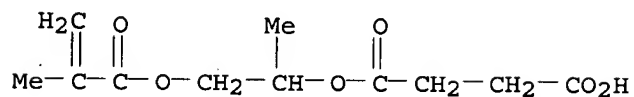
CMF C14 H20 O4



CM 5

CRN 23128-79-2

CMF C11 H16 O6



=> d his

10525429f.trn

(FILE 'HOME' ENTERED AT 11:54:08 ON 18 APR 2007)

FILE 'REGISTRY' ENTERED AT 11:57:01 ON 18 APR 2007

L1 STRUCTURE UPLOADED
L2 1 S L1
L3 18 S L1 SSS FULL

FILE 'HCAPLUS' ENTERED AT 11:57:32 ON 18 APR 2007

L4 8 S L3

FILE 'REGISTRY' ENTERED AT 12:01:49 ON 18 APR 2007

L5 STRUCTURE UPLOADED
L6 0 S L5
L7 0 S L5 SSS FULL
L8 STRUCTURE UPLOADED
L9 1 S L8
L10 18 S L8 SSS FULL
L11 STRUCTURE UPLOADED
L12 50 S L11
L13 2434 S L11 SSS FULL

FILE 'HCAPLUS' ENTERED AT 12:05:26 ON 18 APR 2007

L14 8 S L10
L15 1388 S L13
L16 101 S L15 AND CYANO
L17 3 S L16 AND ADAMANTANE

=> s l14 and py<=2004
25017441 PY<=2004
L18 0 L14 AND PY<=2004

=> log y

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

73.57

824.73

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)

SINCE FILE

TOTAL

ENTRY

SESSION

CA SUBSCRIBER PRICE

-8.58

-14.82

STN INTERNATIONAL LOGOFF AT 12:08:47 ON 18 APR 2007